L Number	Hits	Search Text	DB	Time stamp
2	4486	(250/310,311,309,492.22).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:10
3	43356	(SEM or (scanning adj electron adj microscope))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:11
4	30513	((SEM or (scanning adj electron adj microscope))) and (observ$6 or monitor$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:07
5	11020	(((SEM or (scanning adj electron adj microscope))) and (observ$6 or monitor$4)) and exposure	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:12
6	200	((((SEM or (scanning adj electron adj microscope))) and (observ$6 or monitor$4)) and exposure) and ((obtain$4 or detect$5) with imag$5 with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:14
7	37	(((((SEM or (scanning adj electron adj microscope))) and (observ$6 or monitor$4)) and exposure) and ((obtain$4 or detect$5) with imag$5 with (resist or photoresist))) and ((edge near width) or (pattern near width))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:15
8	18	((((((SEM or (scanning adj electron adj microscope))) and (observ$6 or monitor$4)) and exposure) and ((obtain$4 or detect$5) with imag$5 with (resist or photoresist))) and ((edge near width) or (pattern near width))) and calculat$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:15
9	0	((((((SEM or (scanning adj electron adj microscope))) and (observ$6 or monitor$4)) and exposure) and ((obtain$4 or detect$5) with imag$5 with (resist or photoresist))) and ((edge near width) or (pattern near width))) and diminsion$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:16
10	29	((((((SEM or (scanning adj electron adj microscope))) and (observ$6 or monitor$4)) and exposure) and ((obtain$4 or detect$5) with imag$5 with (resist or photoresist))) and ((edge near width) or (pattern near width))) and dimension$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:18
11	29	((((((SEM or (scanning adj electron adj microscope))) and (observ$6 or monitor$4)) and exposure) and ((obtain$4 or detect$5) with imag$5 with (resist or photoresist))) and ((edge near width) or (pattern near width))) and characteristic) and pattern	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:18
12	7	(((((((SEM or (scanning adj electron adj microscope))) and (observ$6 or monitor$4)) and exposure) and ((obtain$4 or detect$5) with imag$5 with (resist or photoresist))) and ((edge near width) or (pattern near width))) and characteristic) and pattern) and model	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:19

13	5	((((((((((SEM or (scanning adj electron adj microscope))) and (observ$6 or monitor$4)) and exposure) and ((obtain$4 or detect$5) with imag$5 with (resist or photoresist))) and ((edge near width) or (pattern near width))) and characteristic) and pattern) and model) and (correct$4 with exposure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:35
14	1909	((observ$6 or monitor$4) near4 process$4) and ((critical$4 or characteristic) near4 dimension$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:09
15	316	(((observ$6 or monitor$4) near4 process$4) and ((critical$4 or characteristic) near4 dimension$4)) and ((SEM or (scanning adj electron adj microscope)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:10
16	119	((((observ$6 or monitor$4) near4 process$4) and ((critical$4 or characteristic) near4 dimension$4)) and ((SEM or (scanning adj electron adj microscope)))) and (imag$4 with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:11
17	17	"117" and ((edge or pattern) near4 width)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:12
18	6	("117" and ((edge or pattern) near4 width)) and exposure	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:13
19	5	(("117" and ((edge or pattern) near4 width)) and exposure) and correct$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:13
21	4	(((("117" and ((edge or pattern) near4 width)) and exposure) and correct$4) and pattern$4) and calculat$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:16
22	1	((((("117" and ((edge or pattern) near4 width)) and exposure) and correct$4) and pattern$4) and calculat$5) and (ion or electron or charged-particle or (charged adj particle))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:16
20	5	((("117" and ((edge or pattern) near4 width)) and exposure) and correct$4) and pattern$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:22
24	1873	(process$4 with monitor$4) and (SEM or (scanning adj electron adj microscop$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:37
25	807	((process$4 with monitor$4) and (SEM or (scanning adj electron adj microscop$1))) and exposure	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:38
26	198	(((process$4 with monitor$4) and (SEM or (scanning adj electron adj microscop$1))) and exposure) and ((critical$4 or characteristic$4) near dimension$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:39

27	139	((((process$4 with monitor$4) and (SEM or (scanning adj electron adj microscop$1))) and exposure) and ((critical$4 or characteristic$4) near dimension$4)) and correct$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:40
28	136	(((((process$4 with monitor$4) and (SEM or (scanning adj electron adj microscop$1))) and exposure) and ((critical$4 or characteristic$4) near dimension$4)) and correct$4) and ((charged adj particle) or electron)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:41
29	43	((((((process$4 with monitor$4) and (SEM or (scanning adj electron adj microscop$1))) and exposure) and ((critical$4 or characteristic$4) near dimension$4)) and correct$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:42
30	42	(((((((process$4 with monitor$4) and (SEM or (scanning adj electron adj microscop$1))) and exposure) and ((critical$4 or characteristic$4) near dimension$4)) and correct$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)) and (calculat$5 or comput$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:43
31	41	((((((((process$4 with monitor$4) and (SEM or (scanning adj electron adj microscop$1))) and exposure) and ((critical$4 or characteristic$4) near dimension$4)) and correct$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)) and (calculat$5 or comput$4)) and focus$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:44
32	41	(((((((((process$4 with monitor$4) and (SEM or (scanning adj electron adj microscop$1))) and exposure) and ((critical$4 or characteristic$4) near dimension$4)) and correct$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)) and (calculat$5 or comput$4)) and focus$4) and (model$4 or referenc$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:44
33	21	((((((((((process$4 with monitor$4) and (SEM or (scanning adj electron adj microscop$1))) and exposure) and ((critical$4 or characteristic$4) near dimension$4)) and correct$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)) and (calculat$5 or comput$4)) and focus$4) and (model$4 or referenc$4)) and (correct$4 with exposure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:45
34	15	(((((((((((process$4 with monitor$4) and (SEM or (scanning adj electron adj microscop$1))) and exposure) and ((critical$4 or characteristic$4) near dimension$4)) and correct$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)) and (calculat$5 or comput$4)) and focus$4) and (model$4 or referenc$4)) and (correct$4 with exposure)) and (monitor$4 near2 process$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:45

| 35 | 9 | ((((((((((((process$4 with monitor$4) and (SEM or (scanning adj electron adj microscop$1))) and exposure) and ((critical$4 or characteristic$4) near dimension$4)) and correct$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)) and (calculat$5 or comput$4)) and focus$4) and (model$4 or referenc$4)) and (correct$4 with exposure)) and (monitor$4 near2 process$4)) and lithograph$4 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/11/17 14:53 |
| 36 | 2 | ((((((((((((process$4 with monitor$4) and (SEM or (scanning adj electron adj microscop$1))) and exposure) and ((critical$4 or characteristic$4) near dimension$4)) and correct$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)) and (calculat$5 or comput$4)) and focus$4) and (model$4 or referenc$4)) and (correct$4 with exposure)) and (monitor$4 near2 process$4)) and lithograph$4) and ((250/310,311,309,492.22).CCLS.) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/11/17 14:53 |